

ABSTRACT OF THE DISCLOSURE

A negative resist composition comprises:

- (A) an alkali-soluble resin;
- (B) a compound capable of generating an acid upon irradiation with a radiation;
- (C) a crosslinking agent capable of crosslinking by the action of an acid; and
- (D) a solvent mixture containing: at least one solvent selected from the group A below; and at least one selected from the group consisting of the group B below and the group C below:
  - group A: a propylene glycol monoalkyl ether carboxylate;
  - group B: a propylene glycol monoalkyl ether, an alkyl lactate, an acetic ester, a chain ketone and an alkyl alkoxypropionate;
  - group C: a  $\gamma$ -butyrolactone, an ethylene carbonate and a propylene carbonate.